

Chemical State Analysis of Si in NaOH Aqueous Solutions

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The most prevalent industrial method for hydrogen production also generates carbon dioxide. Consequently, our focus shifted to hydrogen production through the reaction of silicon (Si) with water (H₂O), a process that does not emit greenhouse gases. In a prior investigation, it was observed that hydrogenated Si undergoes a reduction in zero-valent Si and an increase in the oxide component of Si upon reaction with water [1-4]. Specifically, the formation of SiO(OH)₂, distinct from SiO₂, occurs during this increase in the oxide component. However, in the previous study, Si *K*-edge X-ray Absorption Fine Structure (XAFS) measurements were conducted after the sample had been exposed to air and naturally dried following hydrogen production. In our current study, we employed a solution cell to explore the chemical state of Si in solutions during hydrogen generation.

The XAFS measurements were carried out at BL-13 of SR Center in Ritsumeikan University. A liquid cell was employed to obtain XAFS spectra from the solution using the partial fluorescence yield method. The XAFS measurements for reference samples of Si, SiO₂, and Na₂SiO₃ were also carried out. For Si *K*-edge measurements, the incident energies were modulated using an InSb(111) double crystal monochromator.

Figure 1 illustrates the XAFS spectra obtained from solution cells containing NaOH aqueous solutions with concentrations of 1 wt% along with Si. Spectral analysis indicates that Na₂SiO₃, SiO₂, and Si components are present during the reaction of Si with 1 wt% NaOH solution.

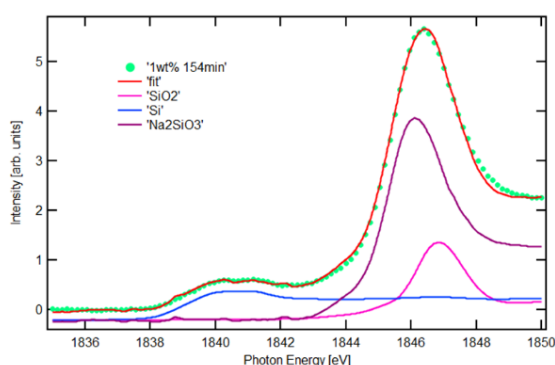


Fig. 1 XAFS spectral analysis for Si in 1 wt% NaOH aqueous solution.

Figure 2 depicts the XAFS spectra obtained from solution cells containing NaOH aqueous solutions with concentrations of 0.09 wt% along with Si. Spectral analysis indicates that SiO₂ and Si components are present during the reaction of Si with 0.09 wt% NaOH solution.

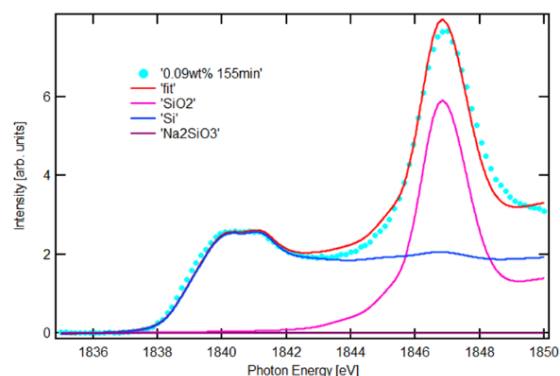
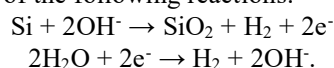
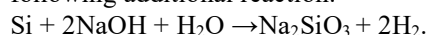


Fig. 2 XAFS spectral analysis for Si in 0.09 wt% NaOH aqueous solution.

Depending on the NaOH concentration, reaction product is found to be different. For the low NaOH concentration (~0.09 wt%), main product of SiO₂ is the results of the following reactions:



For the high NaOH concentration (~1 wt%), additional product of Na₂SiO₃ is the results of the following additional reaction:



References

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- [2] Shoki Kosai, Shiho Fujimura, Shugo Nishimura, Shunsuke Kashiwakura, Kei Mitsuahara, Masaru Takizawa, and Eiji Yamasue, Int. J. Hydrogen Energy **46**, 7722 (2021).
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- [4] S. Nishimura, Master thesis (2022).